



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No. 10/531,208

Confirmation No. 6424

In re Application of

MITSURU UEDA, *et al.*

Art Unit: 1752

Filed: April 14, 2005

Examiner: Sin J. Lee

For: PHOTORESIST BASE MATERIAL, METHOD FOR PURIFICATION THEREOF, AND PHOTORESIST COMPOSITIONS

AMENDMENT

US PATENT AND TRADEMARK OFFICE
Customer Service Window - Mail Stop Amendment
Randolph Building
401 Dulany Street
Alexandria, Virginia 22313-1450

Sir:

In response to the Office Action mailed May 16, 2007, please amend the above-identified patent application as follows: